

ABSTRACT

In a process involving the formation of an
insulating film on a substrate for an electronic device,
5 the insulating film is formed on the substrate surface by
carrying out two or more steps for regulating the
characteristic of the insulating film involved in the
process under the same operation principle. The
formation of an insulating film having a high level of
10 cleanness can be realized by carrying out treatment such
as cleaning, oxidation, nitriding, and a film thickness
reduction while avoiding exposure to the air. Further,
carrying out various steps regarding the formation of an
insulating film under the same operation principle can
15 realize simplification of the form of an apparatus and
can form an insulating film having excellent property
with a high efficiency.